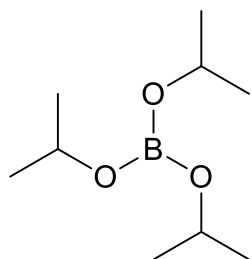


Catalog # 05-1400 Tri-*i*-propylborate, min. 98%



#### Technical Notes

1. Precursor for the preparation of boron oxide films deposited by MOCVD method [1]
2. CVD precursor for the preparation of boron doped single- [2] and multi-walled carbon nanotubes [3]
3. CVD precursor for the preparation of boron doped titanium dioxide for photocatalytic water reduction and oxidation [4-5]
4. Precursor for the preparation of B-doped ZnO transparent conductive oxides films deposited by ALD [6-7]

#### References:

1. *Thin Solid Films* **2004**, 464-465, 164
2. *J. Mater. Chem.*, **2008**, 18, 5676
3. *Phys. Status Solidi B*, **2009**, 246, 2518
4. *Phys. Chem. Chem. Phys.*, **2013**, 15, 16788
5. *J. Mater. Chem. A*, **2017**, 5, 10836
6. *J. Mater. Chem. C*, **2015**, 3, 3095
7. *Sol. Energy Mater. Sol. Cells* **2017** asap publication to be updated